# Effect of TMS (nanostructured silicon dioxide) on growth of Changbai larch seedlings

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Abstract The roots of 200 one-year-old Changbai Larch ( $Larix\ olgensis$ ) seedlings were soaked for 6 hours at the TMS concentrations of 2000, 1000, 500, 250, 125, and 62  $\mu$ L·L·¹. Mean seedling height, root collar diameter, main root length and number of lateral roots were measured every 15 days during growing season from May 30 to Oct. 20. Experimental results showed that TMS treatments greatly promoted seedling growth and improved seedling quality. The treatment by 500  $\mu$ L·L·¹¹ TMS produced the best result , for which the mean height, root collar diameter, main root length, and the number of lateral roots of seedlings were increased by 42.5 %, 30.7%, 14.0%, and 31.6%, respectively, compared to that of the control seedlings. As to seedling quality, grade-I seedling and grade-II seedlings were fifty-fifty, and no grade-III seedlings was found. The treatment by 500  $\mu$ L·L·¹¹ TMS resulted in the highest chlorophyll concentration

Keywords: Changbai Larch; Larix olgensis; Seedling production, Nanostructured silicon dioxide

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#### Introduction

TMS is nanostructured silicon dioxide manufactured by Beijing Luming Institute of Biotechnology and used as a plant regulator. Nanostructured silicon dioxide can form a binary film at cell wall after absorption, which can prevent the infection of fungi,, bacteria, and nematode, reduce plant transpiration, increase disease resistance, and improve plant growth under the stresses of high temperature and humidity. Disease is a major threat to seedling production. Nanostructured silicon dioxide can greatly enhance cell wall rigidity (Wang 2002b) and improve plant resistance to stresses including disease, low temperature, and drought (Wang 1999).

Silicon is an element required in number of metabolic and physiological activities in plants. Research shows that application of silicon fertilizer in silicon-deficient soil can promote plant growth, enhance resistance to disease, cold, and heavy metals of manganese, iron, aluminum, and copper, and increase photosynthesis. Silicon fertilization promotes the absorption of potassium and restricts the absorption of sodium, which therefore increases potassium/sodium selection ratio, helps the accumulation of potassium, nitrogen, and sulphur in plants, and improves

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In recent years, silicon fertilizer is widely used to increase production and to enhance plant stress resistance in agricultural crops (wheat, corn, peanut, and cereal crops), vegetable production (cucumber and radish), and fruit tree cultivation (cherry and apple). In production of forest seedlings, nanostructured silicon dioxide can promote seedling growth and root development and increase resistance to disease. Research in the USA shows that addition of silicon in conifer tissue culture promotes seedling growth (Emadian 1989). However, little information is available on the effects of nanostructured silicon dioxide on tree growth in both physiological research and field experiments. The mechanism of how nanostructured silicon dioxide affects tree growth is not clear. The objective of this study is to determine the effects of nanostructured silicon dioxide in larch seedling production. The experiment was carried out in Hongshi Forest Co. and expected results were obtained.

### Materials and methods

Experimental site is located at Dongxing Forest Nursery, Hongshi Forest Co. Annual mean temperature is 4.5 °C, Ten year-mean cumulative temperature above 5 °C is 2578 °C. The frost-free period is 140 days. Mean annual precipitation is 900 mm. Soil type is dark forest soil. Seedbed is 1 m x 10 m, orientated at north-south direction.

The experimental materials were one-year old Changbai larch (*Larix olgensis*) seedlings. Roots were soaked for 6 hours at the TMS concentrations of 2000, 1000, 500, 250, 125, 62  $\mu$ L·L<sup>-1</sup> and 0  $\mu$ L·L<sup>-1</sup> (no TMS control). Two hun-

dred seedlings were treated at each concentration and a total of 1400 seedlings uniform in size were used. There were four blocks and each block contained 7 treatments (6 treated groups and 1 untreated control). The purpose of blocking was to minimize the systematic errors caused by the change of soil condition.

Each of the planted seedlings was measured for height and RCD (root collar diameter) at the time of planting. Then measurement was carried out every half month until harvest on October 20 when main root length and number of lateral roots were determined.

## Results

## Seedling growth

Mean seedling height, RCD, main root length, and number of lateral roots calculated from 200 treated seedlings were shown in Table 1. Fast increase in both height and RCD occurred in late July (Table 1). The increased growth stops in late August and RCD growth completes in mid-September.

Table 1. Measurements of growth of *Larix olgensis* seedlings treated with different concentrations of TMS (nanostructured silicon dioxide) (n=200)

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Concentration May 30		/ 30	June 15		June 30		July 15		July 30	
of TMS	Mean	Mean	Mean	Mean	Mean	Mean	Mean	Mean	Mean	Mean
/ μL · L <sup>-1</sup>	height	RCD	height	RCD	height	RCD	height	RCD	height	RCD
62	10.1	0.17	11.7	0.20	16.0	0.24	20.1	0.26	28.1	0.32
130	10.7	0.18	11.7	0.22	16.1	0.24	21.1	0.27	28.4	0.31
250	8.5	0.16	9.9	0.20	15.6	0.23	19.6	0.26	29.2	0.32
500	8.8	0.17	11.0	0.20	18.5	0.24	23.8	0.29	33.6	0.34
1000	9.6	0.20	12.0	0.23	17.6	0.28	21.5	0.30	30.8	0.38
2000	9.7	0.17	11.0	0.21	15.4	0.23	19.3	0.24	27.9	0.32
Control	8.5	0.15	9.8	0.18	13.0	0.22	16.1	0.22	23.4	0.27
Concentration	Aug 15		Aug 30		Sep15		Sep 30		Roots on Oct 20	
of TMS	Mean	Mean	Mean	Mean	Mean	Mean	Mean	Mean	Main root	Number of
/ μL · L <sup>-1</sup>	height	RCD	height	RCD	height	RCD	height	RCD	length	lateral roots
62	30.7	0.36	31.3	0.39	31.5	0.42	31.5	0.43	45.0	9
130	33.9	0.34	35.6	0.39	37.0	0.44	37.6	0.45	47.0	9
250	30.7	0.35	35.7	0.41	35.9	0.45	35.9	0.45	52.0	8
500	38.4	0.36	40.1	0.42	40.3	0.47	40.3	0.48	52.5	10
1000	35.3	0.43	37.0	0.48	37.3	0.51	37.3	0.51	50.0	11
2000	32.2	0.36	34.3	0.43	34.3	0.46	34.3	0.46	48.0	9
Control	26.7	0.31	28.7	0.35	28.7	0.38	28.7	0.38	46.0	8

Fifty seedlings were randomly selected from the total of 200 seedlings for the treatment of 500  $\mu$ L L <sup>1</sup> TMS and the control treatment. Height, RCD, main root length, and number of lateral roots were measured on each of the sampled seedlings for statistical comparison. Student t test was used to compare the difference between the 500 $\mu$ L L <sup>1</sup> treatment (x<sub>1</sub>) and untreated control (x<sub>2</sub>).

$$t = (\bar{x}_i - \bar{y}_i)/sqrt(S_{x_i}^2/n + S_{y_i}^2/n)$$

The calculated t values are 13.90 for the height of seed-ling, 6.69 for RCD, 6.83 for main root length, and 6.45 for the number of lateral roots. All the calculated t values are greater than the critical t value at 0.01 level (2.66), indicating a significant difference between  $500\mu L \cdot L^{-1}$  treatment and the control. The treatment of  $500\mu L \cdot L^{-1}$  TMS produced the best result , for which the mean height, root collar diameter, main root length, and the number of lateral roots were increased by 42.5%, 30.7%, 14.0%, and 31.6%, respectively, compared to the control seedlings (Tables 2).

# Chlorophyll content

Chlorophyll content was determined from the mid-crown needles of 15 seedlings randomly sampled from 50 seedlings of each treatment. The mean chlorophyll concentration is presented in the Table 3. The treatment by 500  $\mu L \cdot L^{-1}$  TMS resulted in the highest chlorophyll concentration. Visual assessment also indicates that the needles of seedlings treated by  $500\mu L \cdot L^{-1}$  TMS were darker in color than other treatments.

# **Economic analysis**

The planting density of transplanted Changbai larch seedlings is  $250/m^2$ . Seedling grading system requires >35 cm in height and >0.5 cm in RCD for grade I seedlings, 25-35 cm in height and 0.35-0.5 cm in RCD for grade II seedlings, and <25 cm in height and <0.35 cm in RCD for grade III seedlings. The 500  $\mu$ L·L<sup>-1</sup>-treated group produces 50% seedling in grade I, 50% in grade II, and 0% seedlings in grade III, while no-TMS control group has 0% seedling in grade I, 54% in grade II, and 46% in grade III. The growth

of best seedlings in the control group is equivalent to that of poorest TMS-treated seedlings. The grade I seedlings are priced at 0.17-0.20 Yuan/seedling and grade II at 0.12-0.15 Yuan/seedling. The economic gain is therefore 12.50 Yuan/m² based on the calculation of the seedling density of 250/m². TMS is sold at 0.01 Yuan/g and therefore, the cost

of using TMS in seedling production is 0.015 Yuan/ m². The provincial government requires that grade III seedling can not be used for plantation and another year of cultivation at nursery is needed. All the 2-year old transplants reach grade II standards under TMS treatment, so TMS treatment lead to a significant economic benefit.

Table 2. Statistical comparison on growth between seedlings treated with 500 μL·L<sup>-1</sup> TMS and those in control group

	Growth	of seedlings	treated with 500	) μL · L <sup>-1</sup>	Seedlings (n=50)	Growth of seedlings in control			
Seedlings (n=50)	Height / cm	RCD /cm	Main root length /cm	Number of lateral roots		Height /cm	RCD /cm	Main root length /cm	Number of lateral roots
Mean $\overline{X}_i$	40.87	0.4896	52.89	10.82	Mean $\overline{y}_i$	28.68	0.3746	46.38	8.22
STDEV $S_{x_i}$	5.106	0.100	5.934	2.362	STDEV $S_{v}$	3.519	0.069	3.187	1.595

Table 3. Chlorophyll content (mg/g Fresh Weight, N=15)

Concentration of TMS	665	645	Chlorophyll	Chlorophyll	Total
/μL·L <sup>-1</sup>	Wavelength	Wavelength	a	b	(a+b)
Control	0.9	0.44	0.25616	0.1466	0.40276
62	1.8	1.1	0.497525	0.41915	0.916675
125	3.6	2.1	1.001775	0.78105	1.782825
250	8.5	4.2	2.4163	1.41	3.8263
500	11.2	5.2	3.2063	1.6666	4.8729
1000	5.6	3.8	1.52245	1.5203	3.04275
2000	2.4	1.3	0.674575	0.46345	1.138025

#### **Conclusions**

The best TMS concentration for larch seedling production is  $500\mu\text{L}\cdot\text{L}^{-1}$  with root dipping for 6 hours;

Seedlings treated TMS have 50% in grade I, 50% in grade II, and 0% in grade III. Two-year old seedlings can all meet the standards for field planting;

There is a significant economic gain with the use of TMS in larch seedling production.

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